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| APPLICATION NO.   | FILING DATE     | FIRST NAMED INVENTOR    | ATTORNEY DOCKET NO.   | CONFIRMATION NO. |
|---|-----------------|-------------------------|-----------------------|------------------|
| 10/707,805  | 01/13/2004      | Yi-Nan Chen             | NTCP0027USA           | 1804             |
| 27765   | 7590 08/24/2004 | ·                       | EXAM                  | INER             |
| NAIPO (NORTH AMERICA INTERNATIONAL PATENT OFFICE)<br>P.O. BOX 506<br>MERRIFIELD, VA 22116 |                 |                         | GEBREMARIAM, SAMUEL A |                  |
|   |                 |                         | ART UNIT              | PAPER NUMBER     |
|   |                 |                         | 2811                  |                  |
|   |                 | DATE MAILED: 08/24/2004 |                       |                  |

Please find below and/or attached an Office communication concerning this application or proceeding.

|  | Application No.   | Applicant(s) |  |  |  |  |
|--|---|--------------|--|--|--|--|
|  | 10/707,805  | CHEN ET AL.  |  |  |  |  |
| Office Action Summary  | Examiner  | Art Unit     |  |  |  |  |
|  | Samuel A Gebremariam  | 2811         |  |  |  |  |
| The MAILING DATE of this communication appears on the cover sheet with the correspondence address<br>Period for Reply  |   |              |  |  |  |  |
| A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 1 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.  - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.  - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b). |   |              |  |  |  |  |
| Status   |   |              |  |  |  |  |
| 1) Responsive to communication(s) filed on   |   |              |  |  |  |  |
| ·  |   |              |  |  |  |  |
| 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.   |   |              |  |  |  |  |
| Disposition of Claims  |   |              |  |  |  |  |
| 4) ☐ Claim(s) 1-18 is/are pending in the application. 4a) Of the above claim(s) is/are withdray 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) 1-18 are subject to restriction and/or example and the specification is objected to by the Examine 10) ☐ The drawing(s) filed on is/are: a) ☐ acceptable above.   | vn from consideration. election requirement.  | Examiner.    |  |  |  |  |
| •  | 10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.  Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a). |              |  |  |  |  |
| Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).  11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.   |   |              |  |  |  |  |
| Priority under 35 U.S.C. § 119   |   |              |  |  |  |  |
| <ul> <li>12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).</li> <li>a) All b) Some * c) None of:</li> <li>1. Certified copies of the priority documents have been received.</li> <li>2. Certified copies of the priority documents have been received in Application No.</li> <li>3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).</li> <li>* See the attached detailed Office action for a list of the certified copies not received.</li> </ul>   |   |              |  |  |  |  |
| Attachment(s)  |   |              |  |  |  |  |
| <ol> <li>Notice of References Cited (PTO-892)</li> <li>Notice of Draftsperson's Patent Drawing Review (PTO-948)</li> <li>Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)<br/>Paper No(s)/Mail Date</li> </ol>  | 4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:  |              |  |  |  |  |

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## **DETAILED ACTION**

## Election/Restrictions

1. Restriction to one of the following inventions is required under 35 U.S.C. 121:

- I. Claims 1-8, drawn to semiconductor integrated circuit device, classified in class 257, subclass 301.
  - II. Claims 9-18, drawn to a method of forming integrated circuit device, classified in class 438, subclass 100+.

The inventions are distinct, each from the other because of the following reasons:

2. Inventions II and I are related as process of making and product made. The inventions are distinct if either or both of the following can be shown: (1) that the process as claimed can be used to make other and materially different product or (2) that the product as claimed can be made by another and materially different process (MPEP § 806.05(f)). In the instant case the product as claimed can be made by another materially different process, for example in claim 9, depositing a photoresist layer in the recess region and etching the substrate until the height of the substrate reaches below the collar oxide layer using the resist layer as a mask instead of forming a photoresist layer on the dielectric layer, the photoresist having an opening that defines a shallow trench; etching the dielectric layer, the mask layer, and the pad layer through the opening until the substrate is exposed, and etching the substrate by taking the residual mask layer as a hard mask until a surface of the exposed substrate is lower than a top of the collar oxide layer, wherein the conductive layer and the collar oxide layer remain intact.

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3. Because these inventions are distinct for the reasons given above and have acquired a separate status in the art as shown by their different classification, restriction for examination purposes as indicated is proper.

- 4. Applicant is advised that the reply to this requirement to be complete must include an election of the invention to be examined even though the requirement be traversed (37 CFR 1.143).
- 5. Applicant is reminded that upon the cancellation of claims to a non-elected invention, the inventorship must be amended in compliance with 37 CFR 1.48(b) if one or more of the currently named inventors is no longer an inventor of at least one claim remaining in the application. Any amendment of inventorship must be accompanied by a petition under 37 CFR 1.48(b) and by the fee required under 37 CFR 1.17(i).

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Samuel A Gebremariam whose telephone number is (571) 272-1653. The examiner can normally be reached on 8:00am-4:30pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Eddie Lee can be reached on (571) 272-1732. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

SAG August 11, 2004

SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 2800

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